

Practitioner's Docket No. 081468-0307456
Client Reference: P-1794.000-US



PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of: VADIM YEVGENYEVICH BANINE et al.

Application No.: 10/747,613

Confirmation No.: 2894

Filed: December 30, 2003

Group No.: 2881

Examiner:

For: LITHOGRAPHIC APPARATUS AND RADIATION SOURCE COMPRISING A DEBRIS-MITIGATION SYSTEM AND METHOD FOR MITIGATING DEBRIS PARTICLES IN A LITHOGRAPHIC APPARATUS

Commissioner for Patents

P.O. Box 1450

Alexandria, VA 22313-1450

SUPPLEMENTAL APPLICATION DATA SHEET
37 C.F.R. § 1.76(c)

The following information on the Application Data Sheet is changed as indicated:

BIBLIOGRAPHIC DATA

1. Assignee information is being modified.

The assignee of this application is:

ASML NETHERLANDS B.V.

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Extent of interest of assignee in application: ENTIRE RIGHT, TITLE AND INTEREST

Date: July 23, 2004

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